

AMENDMENTS TO THE SPECIFICATION

Please replace the sentence that begins on page 2, line 25, with the following rewritten sentence, which is marked up to show changes that have been made:

The exposure apparatus 1000 thus includes a light source section 1013, 1014 that generates the EUV light, an illumination optical system (i.e., the first rotational paraboloid mirror 1004, the reflection integrator 1005 and the second rotational paraboloid mirror 1006), the reflection mask 1007, the projection optical system that is comprised of plural mirrors 1008, the wafer 1009, the mask mounted stage 1010, the wafer mounted stage 1011, an alignment mechanism (not shown) for precise alignment between mask and wafer positions, the vacuum chamber 1017 that maintains vacuum of the entire optical system vacuum for reduced attenuations of the EUV light, and an exhaust apparatus (not shown).

Please replace the sentence that begins on page 3, line 21, with the following rewritten sentence, which is marked up to show changes that have been made:

The projection optical system that is comprised of plural mirrors 1008 images, on the wafer 1009, the EUV light that has information of a circuit pattern reflected by the reflection mask 1007.

Please replace the sentence that begins on page 3, line 25, with the following rewritten sentence, which is marked up to show changes that have been made:

The projection optical system that is comprised of plural mirrors 1008 is configured to have excellent imaging performance in an off-axis, thin arc area (i.e., apart from an optical-axis center).

Please replace the paragraph that begins on page 4, line 6, with the following rewritten paragraph, which is marked up to show changes that have been made:

The projection optical system that is comprised of plural mirrors 1008, which are ~~is comprised of plural~~ multilayer mirrors, ~~and~~ is configured to project a reduced size of pattern on the mask 1007 onto the wafer 1009 surface. The projection optical system that is comprised of plural mirrors 1008 typically forms an image-side telecentric system, and usually provides an object side (or the reflection mask side) with a non-telecentric structure so as to avoid physical interference with the illumination light incident upon the reflection mask 1007.

Please replace the sentence that begins on page 5, line 11, with the following rewritten sentence, which is marked up to show changes that have been made:

The projection optical system that is comprised of plural mirrors 1008 is configured to project an image of the secondary light sources onto an entrance pupil surface, and thereby meets the Kohler's illumination conditions.

Please replace the sentence that begins on page 5, line 23, with the following rewritten sentence, which is marked up to show changes that have been made:

The projection optical system that is comprised of plural mirrors 1008 is configured to project an image of the secondary light sources onto its pupil surface.

Please replace the sentence that begins on page 16, line 4, with the following rewritten sentence, which is marked up to show changes that have been made:

As shown in FIG. 3A, when approximately parallel EUV light ~~[[11]]~~ 10' is incident upon the integrator 11a having plural cylindrical surfaces, the secondary light source is formed near the integrator surface and the EUV light radiated from this secondary light source has a cone angular distribution.

Please replace the sentence that begins on page 21, line 24, with the following rewritten sentence, which is marked up to show changes that have been made:

The projection optical system ~~1008~~ 18 provides an object side (or the reflection mask side) with a non-telecentric structure so as to avoid physical interference with the illumination light incident upon the reflection mask 16, and the instant embodiment inclines the image-side principal ray, for example, by about 6.degree. relative to the normal direction of the mask 16.

Please replace the sentence that begins on page 23, line 22, with the following rewritten sentence, which is marked up to show changes that have been made:

The masking blade 13 includes four light-shielding plates 801, 802, 803 and 804, the upper and lower light-shielding plates 803 and 804 shield light at both ends of the arc illuminated area 812 in the arc slit opening ~~[[812]]~~ 811, and define a longitudinal width (or a scan width) of the exposed area 702 shown in FIG. 7A.

Please replace the sentence that begins on page 25, line 6, with the following rewritten sentence, which is marked up to show changes that have been made:

The masking imaging system 14 is an imaging optical system that uses the above masking blade 13 as an image surface, and ~~[[the]]~~ a reflection mask ~~[[16]]~~ (not labeled, at a position 102 in the figure) as an image surface, and includes reflective multilayer mirrors.

Please replace the sentence that begins on page 26, line 27, with the following rewritten sentence, which is marked up to show changes that have been made:

Since the optical axis ~~[[18X]]~~ of the projection optical system is parallel to the normal to the mask surface, an angle between the optical axis ~~[[18X]]~~ of the projection optical system and the mask-side principal ray of the projection optical system 18.